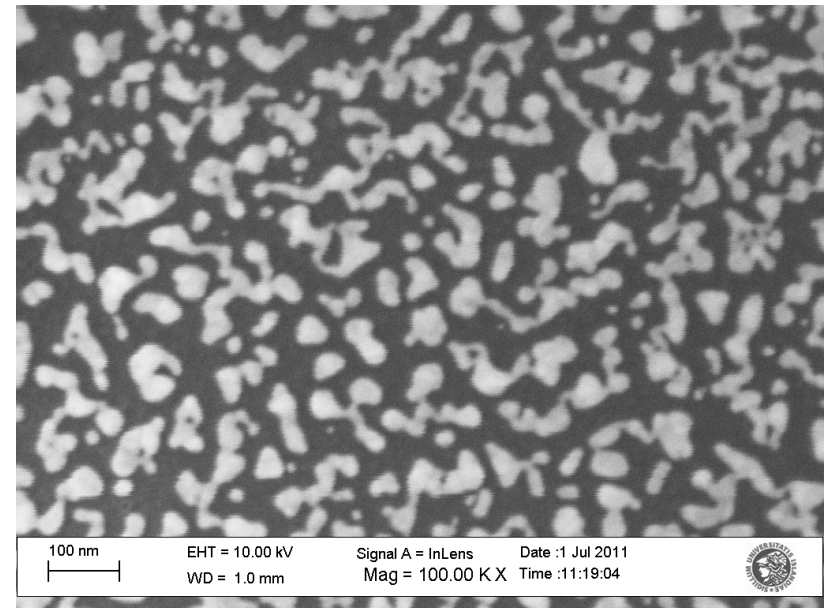




# Preparation of Nanostructures

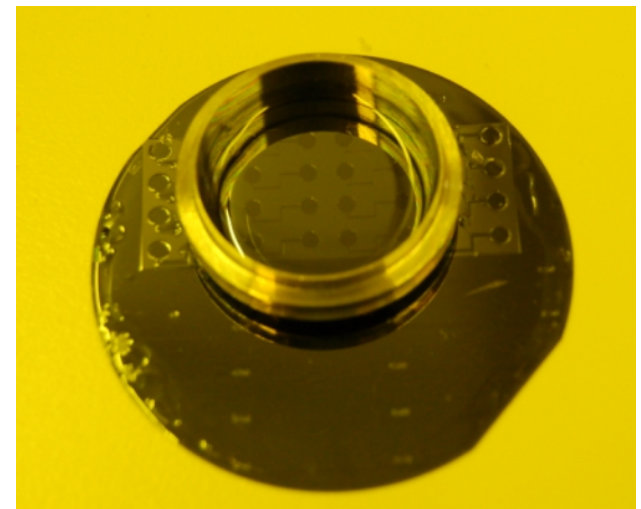
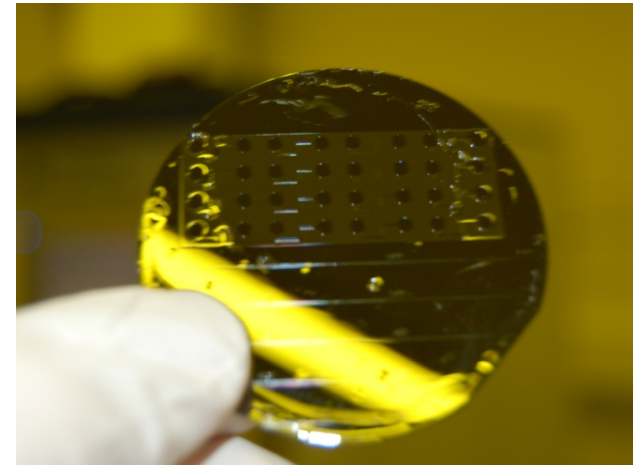


SEM picture of 7nm thick gold on a polymer substrate

Guðmundur Kári Stefánsson  
19th November 2012



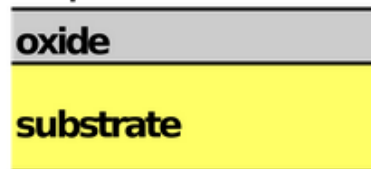
- Patterning techniques
- Equipment
- Applications



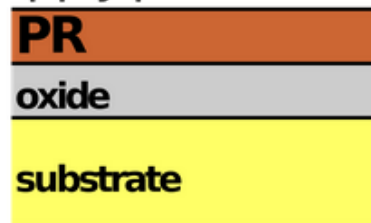


# Overview

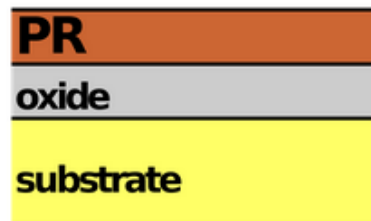
a. Prepare wafer



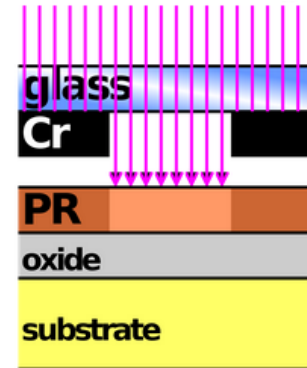
b. Apply photoresist



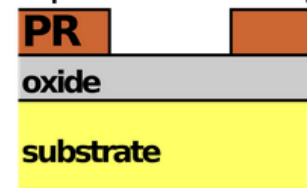
c. Align photomask



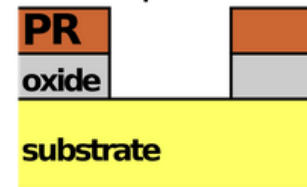
d. Expose to UV light



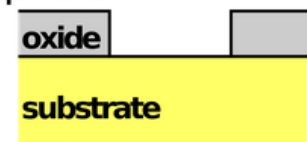
e. Develop and remove photoresist exposed to UV light



f. Etch exposed oxide



g. Remove remaining photoresist

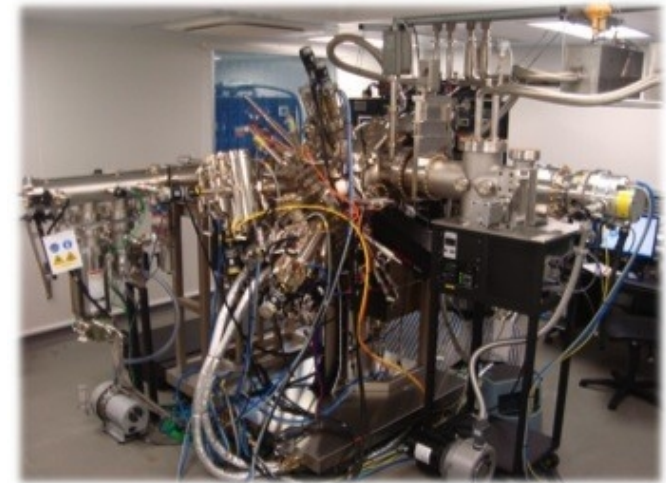
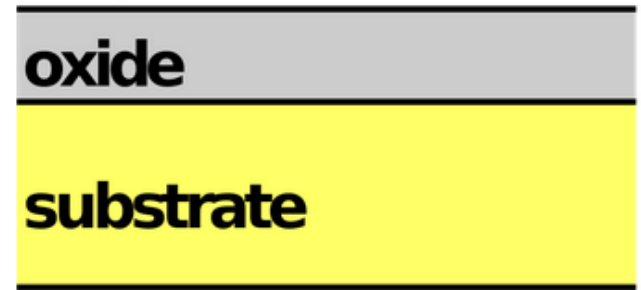




# Preparing the substrate

- Substrate
  - Si, Ge, GaAs/AlGaAs, InGaAs/InP
- Molecular Beam Epitaxy (MBE)
  - A technique to grow crystalline layers
  - High purity ( $>99.999999\%$ )
  - Growth rate: 0.001 - 2 monolayers/sec
- Presence of an oxide layer

## a. Prepare wafer

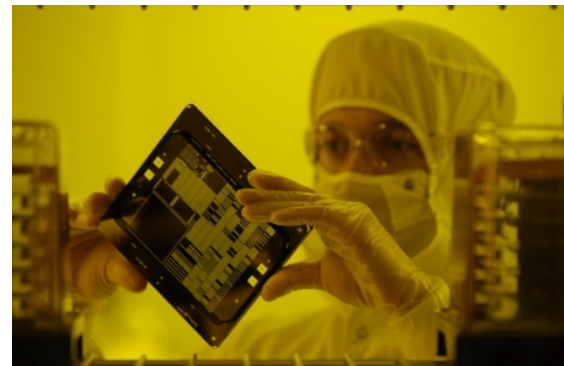


Expensive epitaxy equipment



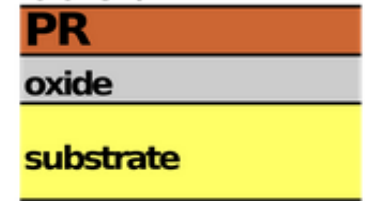
# Lithography

- Transfer of patterns to a UV-sensitive material
- Two main types
  - **Optical lithography** ->
    - Range: ~100nm
    - Fast, relatively cheap
  - E-beam lithography
    - Range: ~5-10nm
    - More expensive
- Photoresist:
  - “+”: Breaks down if illuminated
  - “-”: Hardenes if illuminated

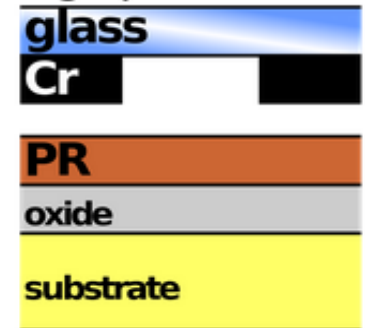


A patterned mask

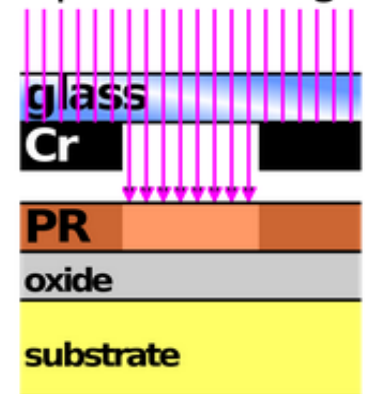
b. Apply photoresist



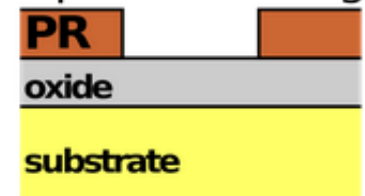
c. Align photomask



d. Expose to UV light

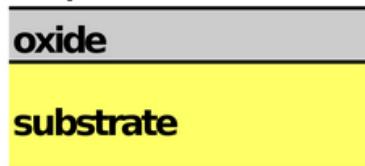


e. Develop and remove photoresist exposed to UV light

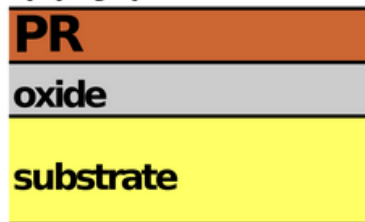




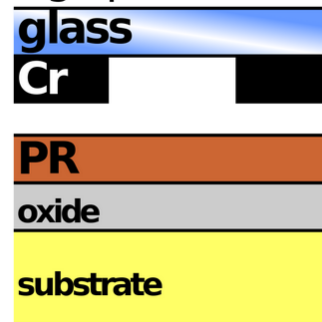
a. Prepare wafer



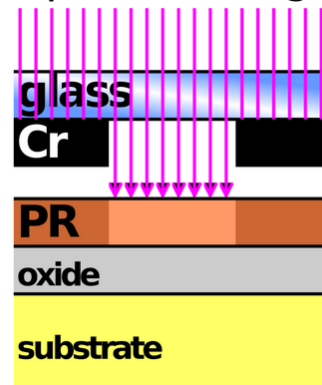
b. Apply photoresist



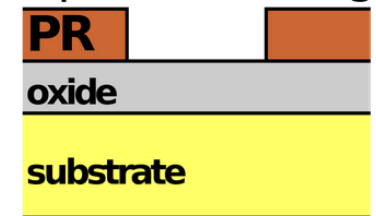
c. Align photomask



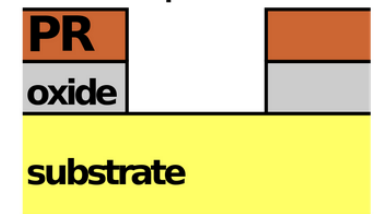
d. Expose to UV light



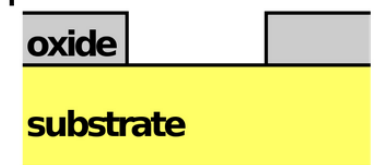
e. Develop and remove photoresist exposed to UV light



f. Etch exposed oxide



g. Remove remaining photoresist



Spinner

Spinner chuck      Compressed air valve



Mask aligner



RIE equipment



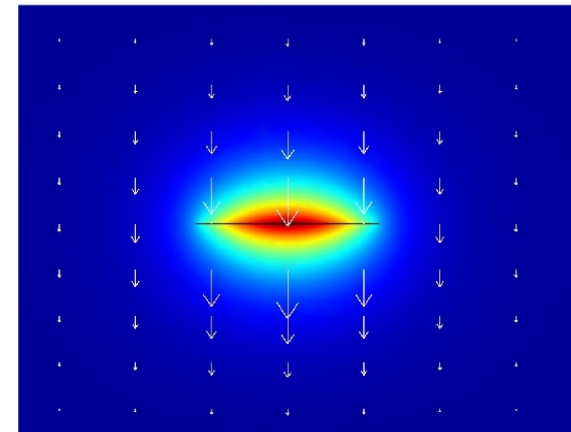


# Applications

- Many applications
- Combine with metal deposition
  - Elaborate multilayer devices
- **Research with KL group**
  - Microfluidics
  - LRSPP Waveguides
  - Fluorescent materials – OLED



Cell imaging

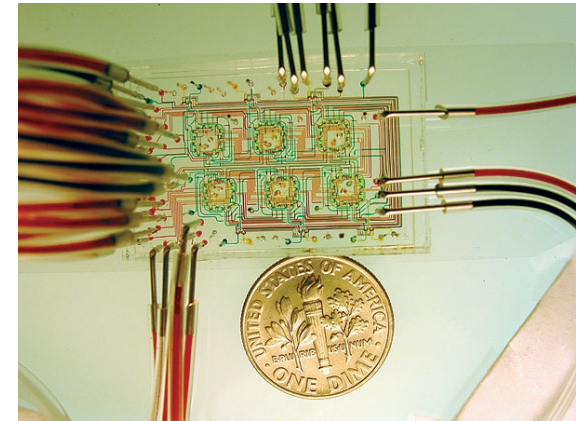


Simulations of LRSPP  
in a gold waveguide

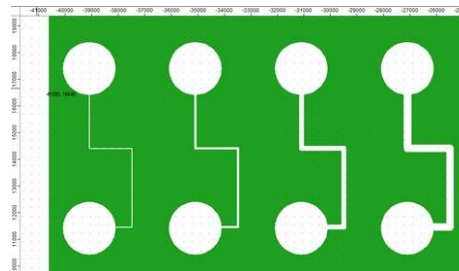


# Microfluidics

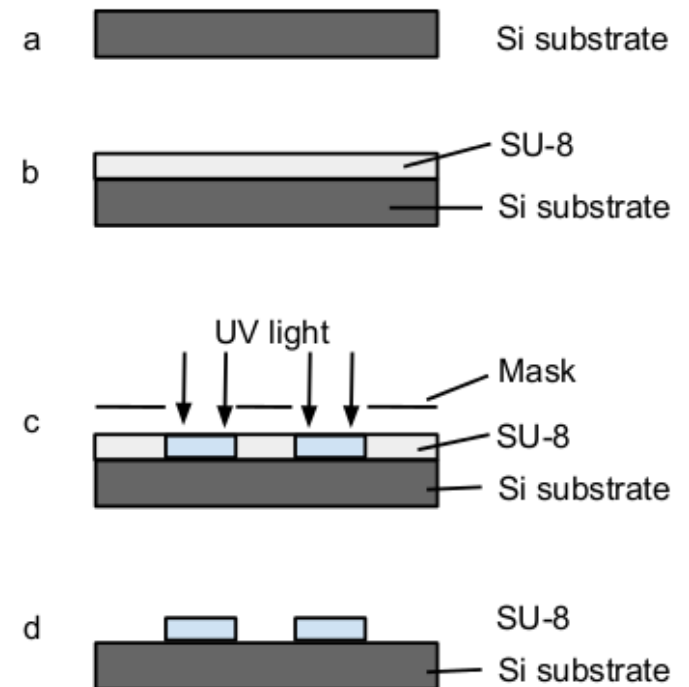
- Control and manipulation of fluids in a sub-millimeter scale
  - Small volumes:  $\mu\text{L}$ ,  $\text{nL}$ ,  $\text{pL}$ ,  $\text{fL}$
- Organic materials
  - SU-8 master mold
  - PDMS circuits
- Integration with optical circuits
  - Biosensing



Microfluidic circuits - “lab on a chip”



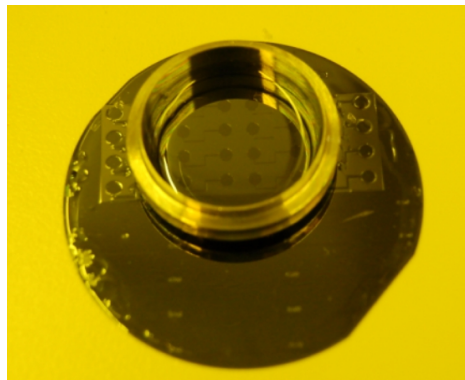
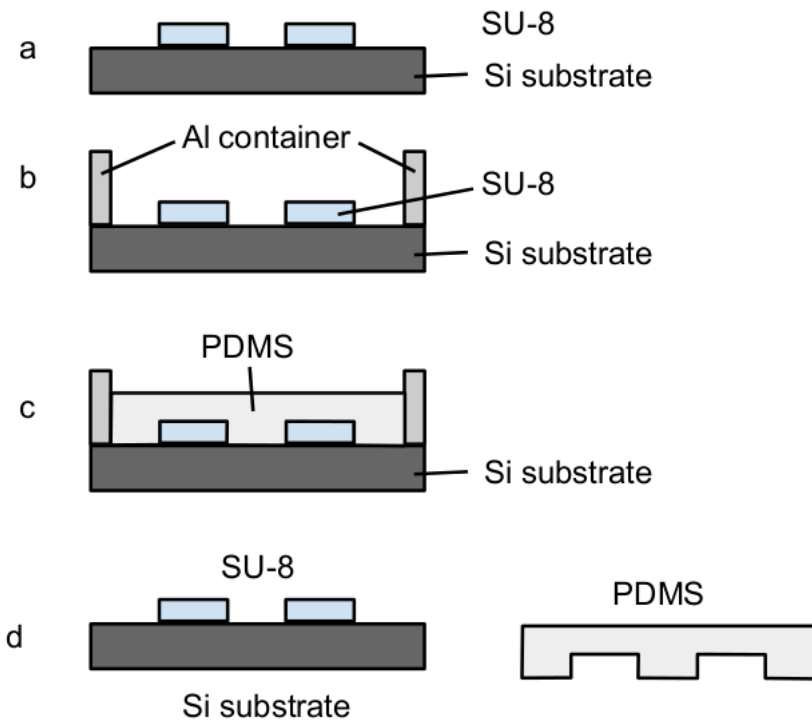
A patterned mask



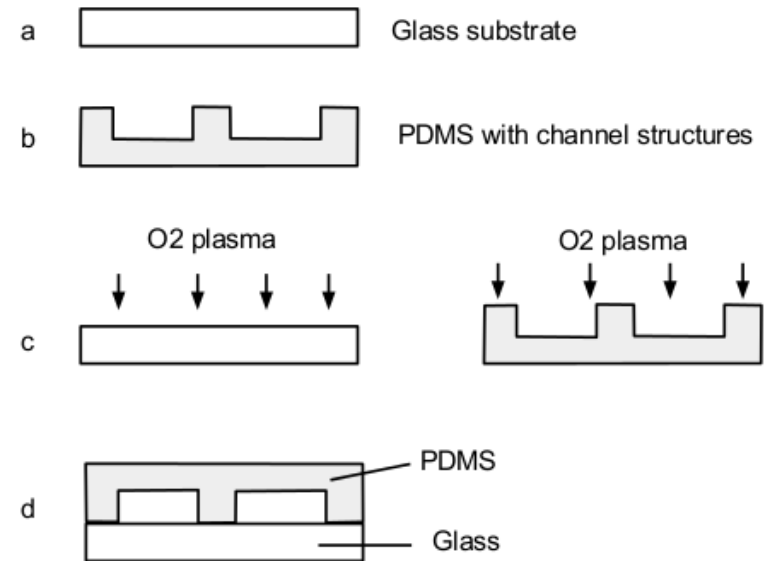


# Microfluidics

## Shaping the PDMS circuits:



## Bonding to a substrate:



## A completed microfluidic device

